CMOS-MEA Chip for Use with CMOS-MEA5000-System

Technical Specifications

Important!
CMOS-MEAs are not symmetrical! Please take care for the correct orientation of the chip. The round edge of the CMOS-MEA has to be in the front on the left side when looking directly to the open CMOS-MEA headstage.

Technical Specifications

- **Temperature**: 0 - 125 °C
- **Dimensions (W x D x H)**: 55 x 55 x 2 mm
- **Base material**: PCB
- **CMOS chip**: glass like surface
- **Track material**: Bonding wires and Au
- **Contact pads**: Au
- **Electrode diameter**: 8 µm
- **Interelectrode distance from center to center**: 16 or 32 µm
- **Active area**: 1.04 mm x 1.04 mm or 2.08 mm x 2.08 mm
- **Flat area (around active area)**: rectangle: 8 mm x 8.5 mm or round: diameter 6 mm
- **Recording electrodes**: 4225 in 65 x 65 layout grid
- **Stimulation electrodes**: 1024 in 32 x 32 layout grid

Sterilization
Before using the CMOS-MEA chip, please sterilize the surface with UV radiation, for example, in a conventional flow box.

Warning: It is not recommended to treat the CMOS chip in plasma cleaner! Plasma treatment may destroy the chip.
CMOS-MEA Chip
for Use with the CMOS-MEA5000-System

Chamber Types combined with a CMOS-MEA Chip:
for the Cell Cultures (-CC),
for Slices (-SCB and -SCA).

Use the Slice Chamber Basic SCB for acute slices on the CMOS-MEA chip. It has a flat rectangle area (8 mm x 8.5 mm) for placing the slice. Please use an external Ag/AgCl electrode to ground the bath.

Use the Slice Chamber Advanced SCA for acute slices on the CMOS-MEA chip. It has a flat rectangle area for placing the slice (8 mm x 8.5 mm) with influx and drain for intensive perfusion. Please use an external Ag/AgCl electrode to ground the bath.

Use the Culture Chamber CC with lid for cell cultures on the CMOS-MEA chip. It has a flat round area (diameter 6 mm) for the cell culture. It is possible to cultivate the cells on the chip in an incubator. A ground electrode is integrated in the CC, an external Ag/AgCl electrode is not necessary.

Please note: The lid has to be sealed with a semipermeable membrane. We recommended ALA MEA-MEM-Sheets from ALA Scientific, Inc., which need to be ordered separately.

Cleaning of the CMOS-MEA Chip

CMOS chips are gently cleaned with detergent Tickopur R36 (5%, Stamm/Berlin, 80 degC), and rinsed with ultrapure water (resistivity: 18 MVcm). Fill hot Tickopur solution (80 °C) with a glass pipette into the CMOS MEA chamber onto the electrode field. Remove the Tickopur solution after 2 minutes by rinsing the chip with ultrapure water.

Use a cotton swab for carefully cleaning the surface, if necessary. Please do not damage the surface mechanically, otherwise the chip will be destroyed.

The following cleaning protocol was used in experiments with retina cells. Please read the paper which is online free available: Axonal Transmission in the Retina Introduces a Small Dispersion of Relative Timing in the Ganglion Cell Population Response from Guenther Zeck, Armin Lambacher, Peter Fromherz (2011).